

EXPOSING APPARATUS AND EXPOSING METHOD, FOR
MASKLESS EXPOSURE OF SUBSTRATE TO BE EXPOSED,
AND PLOTTER AND PLOTTING METHOD FOR
DIRECTLY PLOTTING ON OBJECT TO BE PLOTTED

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ABSTRACT OF THE DISCLOSURE

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An exposing apparatus for irradiating desired spots on a substrate to be exposed relatively moving with respect to two or more light sources arranged along the direction of the relative movement to form a desired exposure pattern using the light sources comprises a control means for controlling the turning-on of only specific light sources out of the two or more light sources at a specific timing.